



Atty. Dkt. No. 047297-0137

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Hisatsugu KURITA *et al.*
Title: SILICON WAFER CLEANING METHOD
Appl. No.: 10/645,911
Filing Date: 08/22/2003
Examiner: Michail Kornakov
Art Unit: 1746
Confirmation No.: 8557

AMENDMENT AND REPLY UNDER 37 CFR 1.116

Mail Stop AF
Commissioner for Patents
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M.K.
11/21/06

Sir:

This communication is responsive to the Final Office Action dated August 3, 2006,
concerning the above-referenced patent application.

Amendments to the Claims are reflected in the listing of claims which begins on
page 2 of this document.

Remarks/Arguments begin on page 3 of this document.

Please amend the application as follows:

Entered
w/RCE
dtd 12/4/06
Kw
12/8/06